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BOOK OF ABSTRACTS

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Barrier Properties of Anodically Formed Nb₂O₅

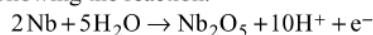
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By cyclic voltammetry and ellipsometry the barrier properties of Nb₂O₅, anodically formed on Nb electrode, in various concentrations of acid and alkaline solutions, have been investigated. The cyclic voltammetry I-E profiles reveal to the active/passive transition, i.e. metal dissolution and then, formation of thin passive film. Upon reversing the potential scan, the current decreases abruptly until it reaches almost of constant value that is several orders of magnitude lower than the first forward scan. This behavior can be considered to be the result of high current efficiency under oxide growth. In active region metal dissolution occurs by reaction



while in the passive region the large current plateau, (Fig.1), is provoked by film thickness grows following the reaction.



The barrier properties of anodically formed Nb₂O₅ in the passive region can most easily interrelated by performing of sequence of cyclic voltammetry measurements in which the final potential is gradually enlarged in each next cycle, Fig.2

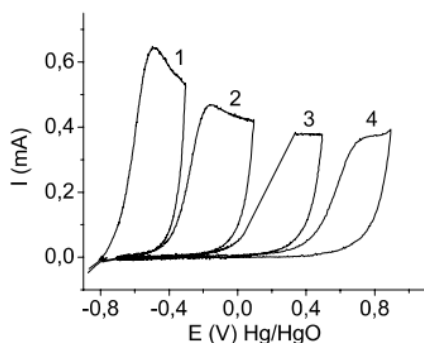


Fig 1. Voltammograms of Nb electrode recorded in 1 M KOH: 1 – first cycle, 2 – second cycle ($v = 50 \text{ mV/s}$)

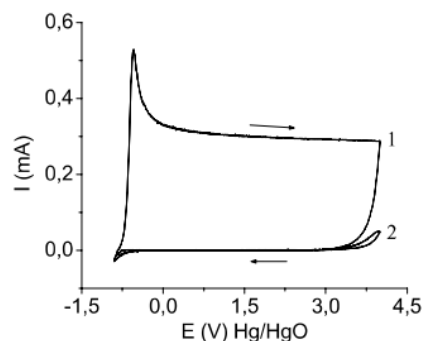


Fig. 2. Voltammograms of Nb electrode recorded in 1 M KOH: 1, 2, 3 and 4 are number of cycles ($v = 50 \text{ mV/s}$)

In fig.2, the anodic oxidation may take place only if the actual potential exceeds the maximum value attained in the previous cycle. The large current plateau almost parallel with E axis indicates linear growth of film thickness with applied potential.

The ellipsometric measurements have shown the linear film thickness grows with applied voltage, even at 100 V, indicating barrier properties not only for thin, but also and for thick film. The coefficient of film thickness growth is approximately 2.3 nm/V